



Future Normal in Semiconductor

2025-02-14(금), 09:00-10:45

좌장: 추후업데이트 예정

D. Thin Film Process Technology 분과

[FC1-D] Atomic Layer Deposition - I

<p>FC1-D-1 09:00-09:15</p>	<p>Catalyst-Assisted Low-Temperature Atomic Layer Deposition of SiO₂ Films and Enhanced Film Quality via <i>In-situ</i> Ozone Treatment Hyekyung Kim, Seo-Hyun Lee, and Woo-Hee Kim Department of Materials Science and Chemical Engineering, Hanyang University</p>
<p>FC1-D-2 09:15-09:30</p>	<p>Effects of TDMAZ Impurity in CpTDMAZ Precursor for ZrO₂ ALD Films Seongmoo Oh¹, Sang-Min Lee¹, Hye-Lee Kim¹, Won-Jun Lee¹, Kwan Hyun Park², Hyun Ki Kim², Kyung Sik Lee², Jung Woo Park², and Jongwan Jung¹ ¹Sejong University, ²Hansol Chemicals</p>
<p>FC1-D-3 09:30-09:45</p>	<p>Comparative Study on Lateral and Vertical Mixing of Atomic Arrangement in Multielement Oxides Grown by Atomic Layer Deposition; a Case Study of Dy-Doped HfO₂ Byung-ha Kwak¹, Ngoc Le Trinh², Wonjoong Kim², Han-Bo-Ram Lee², and Il-kwon Oh^{1,3} ¹Department of Intelligence Semiconductor Engineering, Ajou University, ²Department of Materials Science and Engineering, Incheon National University, ³Department of Electrical and Computer Engineering, Ajou University</p>
<p>FC1-D-4 09:45-10:00</p>	<p>Role of a Cyclopentadienyl Ligand in Hf Precursors Using H₂O or O₃ as Oxidant in Atomic Layer Deposition Youngmin Song¹, Hui-Jin Kim², Su-Jin Kwon³, Soo Hyun Lee³, Bonggeun Shong³, and Il-Kwon Oh^{1,2} ¹Department of Intelligence Semiconductor Engineering, Ajou University, ²Department of Electrical and Computer Engineering, Ajou University, ³Department of Chemical Engineering, Hongik University</p>
<p>FC1-D-5 10:00-10:15</p>	<p>Advanced Atomic Layer Deposition: Metal Oxide Thin Film Growth Using Electric Potential Jae Chan Park¹, Chang Ik Choi¹, Sang Gil Lee², Seung Jo Yoo², Ji Hyun Lee², Kyun Seong Dae², Jae Hyuck Jang², Woo Hee Kim¹, Ji Hoon Ahn¹, and Tae Joo Park¹ ¹Department of Materials Science and Chemical Engineering, Hanyang University, ²Center for Research Equipment, KBSI</p>



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<p>FC1-D-6 10:15-10:30</p>	<p>Influence of Oxidants on the Characteristics of Atomic Layer Deposited TiO₂ Thin Film Jae Hun Hwang¹ and Taeyong Eom² ¹Department of Materials Science and Engineering, Yonsei University, ²Department of Semiconductor System Engineering, Sejong University</p>
<p>FC1-D-7 10:30-10:45</p>	<p>Enhanced Growth Behavior and Electrical Properties of Atomic-Layer-Deposited La₂O₃ film at High Temperature Using Novel Precursor with Discrete Feeding Method Min Soo Shin¹, Jae chan Park¹, Yong min Go², Woo-Hee kim¹, Ji-Hoon Ahn¹, Bo Keun Park², and Tae Joo Park¹ ¹Department of Materials Science and Chemical Engineering, Hanyang University, ²Division of Advanced Materials, KRICT</p>